

## **AMENDMENTS TO THE CLAIMS**

1. (Previously Presented) The semiconductor device of claim 9,

wherein said base contact section is constructed of a repeating structure in a plan view, in which a high impurity concentration region of the second conductivity type and a region of the first conductivity type are arranged in an alternate manner.

2. (Withdrawn) The semiconductor device of claim 9,

wherein said base contact section is constructed of a repeating structure in a plan view, in which a high impurity concentration region of the second conductivity type and a region of the second conductivity type constituting said base region are arranged in an alternate manner.

3. (Cancelled)

4. (Cancelled)

5. (Currently Amended) The semiconductor device of claim 9, wherein an said emitter electrode connected to said emitter region and a said base electrode connected to said base contact section are formed in respective comb structures in which teeth of said emitter electrode and said base electrode are engaged with each other being alternately arranged in an alternate manner.

6. (Cancelled)

7. (Cancelled)

8. (Cancelled)

9. (Currently Amended) A semiconductor device with a bipolar transistor comprising:

a first conductivity type semiconductor layer serving as a collector region;

a base region constituted of a second conductivity type region provided in said first conductivity type semiconductor layer;

an emitter region constituted of a first conductivity type region provided in said base region; and

a base contact section ~~provided oppositely~~ spaced apart from said emitter region in said base region, electrically connected to a base electrode,

wherein said emitter region comprises a plurality of stripe regions and each of said stripe regions is formed so that a plurality of portions of said base region is are exposed at the central portion of each of said stripe regions, said portions being to be segmented into by a plurality of openings arranged along a direction of the stripe, and an emitter electrode is formed so as to be connected to said stripe regions and to cover the exposed portions of said base region via an insulating film on said stripe regions and ~~said exposed portions of said base region.~~

10. (Cancelled)

11. (Cancelled)

12. (Cancelled)